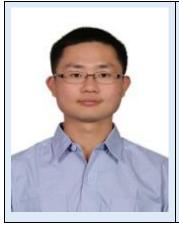
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- B. Journal Paper EI (期刊論文)
- C. Conference Paper (會議論文)
- D. Patent (專利)
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